

an illumination system adapted to illuminate a first mask portion to define a first illumination mode and to illuminate a second mask portion to define a second illumination mode;

a projection system adapted to image at least parts of said first and second mask portions onto said substrate to form at least a portion of said pattern; and

el
a mask mover adapted to move a mask containing said first and second mask portions with respect to the projection system, said mask mover distinctly positioning first and second mask sub-patterns, located at different positions on the mask, in a radiation beam emerging from the illumination system;

wherein at [lest] least one of said first and second illumination modes is a dipolar illumination mode and wherein said apparatus is arranged to image said pattern by at least two exposures using respective said first and second illumination modes and mask sub-patterns.

REMARKS

Applicants respectfully request consideration and allowance of the above-identified application including the foregoing amendment and following remarks.

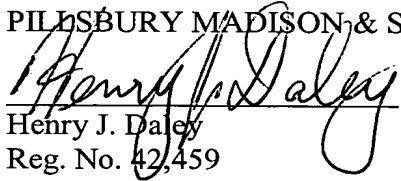
Claims 1-23 are pending in the application.

Applicants amended claim 20 to correct a minor typographical error inadvertently introduced into that claim.

A prompt and favorable Action on the merits is respectfully solicited.

Respectfully submitted,

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